

Query of interest IMN Colloquium "Photolithography"

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Please prioritise as follows and, if suitable, specify your personal interest

[] = not relevant

[x] = relevant

[xx] = of big interest

Substrate Pretreatment (cleaning and adhesion promotion)

Resist Coating Techniques (mechanism, (dis-)advantages, suited resists)

Spin Coating

Spray Coating

Dip coating

Other:

Softbake

What happens in the resist film

too cool, to hot ... optimum parameters

Hotplate or oven?

Other:

Rehydration

Exposure

Spectral sensitivities of resists

Chemical photo reaction

laser writing

N₂-formation

Optimum exposure dose

sub- μ m resolution, wave optics limitations

Grey tone lithography

Anti-reflection coatings

other:

Post Exposure Bake

Standard resists

Chemically amplified resists

Image reversal resists

Negative resists

Other:

Entwicklung

MIF and MIC developers

Development rate and dark erosion

Neutralization by CO₂

Capacity (saturation by developed resist)

Tank- and puddle development

Other:

Hardbake (purpose and parameters)

Thick Resist Processing: Chemically amplified resists

Lift-off processes

Wet tching

Plating

Negative Resist Processing

Other Topics